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Attorney Docket No.: PATENT
SSI-00501

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Maximilian A. Biberger, *et al.*

Serial No.: 09/912,844

Filed: July 24, 2001

For: **HIGH PRESSURE PROCESSING
CHAMBER FOR
SEMICONDUCTOR SUBSTRATE**

) Group Art Unit: 2812

) Examiner:

) **TRANSMITTAL LETTER**

) 260 Sheridan Avenue, Suite 420
) Palo Alto, California 94306
) (650)833-0160

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Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Enclosed please find a Supplemental Information Disclosure Statement, Form PTO-1449, including copies of the references contained thereon, for filing in the U.S. Patent and Trademark Office.

The Commissioner is hereby authorized to charge any additional fee or credit overpayment to our Deposit Account No. 08-1275. **An originally executed duplicate of this transmittal is enclosed for this purpose.**

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 11-19-01

By:

Thomas B. Haverstock
Reg. No.: 32,571

Attorneys for Applicants

CERTIFICATE OF MAILING (37 CFR § 1.8(a))

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to the: Assistant Commissioner for Patents, Washington D.C. 20231

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) **SUPPLEMENTAL INFORMATION**
) **DISCLOSURE STATEMENT**

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Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

The citations listed below, copies attached, may be material to the examination of the above-identified application, and are therefore submitted in compliance with the duty of disclosure defined in 37 C.F.R. §§ 1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

Applicants have become aware of the following printed publications which may be material to the examination of this application:

- U.S. Patent No. 4,788,043;
- U.S. Patent No. 4,944,837;
- U.S. Patent No. 5,013,366;
- U.S. Patent No. 5,068,040;
- U.S. Patent No. 5,143,103;
- U.S. Patent No. 5,185,296;
- U.S. Patent No. 5,213,619;
- U.S. Patent No. 5,215,592;
- U.S. Patent No. 5,236,602;
- U.S. Patent No. 5,237,824;

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- U.S. Patent No. 5,267,455;
- U.S. Patent No. 5,304,515;
- U.S. Patent No. 5,306,350;
- U.S. Patent No. 5,313,965;
- U.S. Patent No. 5,316,591;
- U.S. Patent No. 5,337,446;
- U.S. Patent No. 5,355,901;
- U.S. Patent No. 5,368,171;
- U.S. Patent No. 5,370,740;
- U.S. Patent No. 5,377,705;
- U.S. Patent No. 5,401,322;
- U.S. Patent No. 5,403,621;
- U.S. Patent No. 5,417,768;
- U.S. Patent No. 5,456,759;
- U.S. Patent No. 5,494,526;
- U.S. Patent No. 5,500,081;
- U.S. Patent No. 5,501,761;
- U.S. Patent No. 5,522,938;
- U.S. Patent No. 5,526,834;
- U.S. Patent No. 5,533,538;
- U.S. Patent No. 5,683,977;
- U.S. Patent No. 5,797,719;
- U.S. Patent No. 5,868,856;
- U.S. Patent No. 5,868,862;
- U.S. Patent No. 5,881,577;
- U.S. Patent No. 5,888,050;
- U.S. Patent No. 5,900,354;
- U.S. Patent No. 5,908,510;
- U.S. Patent No. 5,976,264;
- U.S. Patent No. 5,980,648;
- U.S. Patent No. 6,024,801;
- U.S. Patent No. 6,149,828;
- U.S. Patent No. 6,242,165 B1;

- PCT Publication No. WO 99/49998;
- PCT Publication No. WO 01/78911 A1;
- J.B. Rubin et al, "A Comparison of Chilled DI Water/Ozone and Co₂-Based Supercritical Fluids as Replacements for Photoresist-Stripping Solvents," 1998, pp. 308-314, IEEE/CPMT Int'l Electronics Manufacturing Technology Symposium;
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- Russick, E.M. et al., "Supercritical Carbon Dioxide Extraction of Solvent From Micromachined Structures," Supercritical Fluids -- Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp 255-269, 21 Oct 1997;
- McHardy, J. et al., "Progress in Supercritical CO₂ Cleaning," SAMPE Jour., Vol. 29, No. 5, pp. 20-27, September 1993;
- Bok, E. et al., "Supercritical Fluids for Single Wafer Cleaning," Solid State Technology, pp. 117-120, June 1992;
- Hansen, B.N. et al., "Supercritical Fluid Transport -- Chemical Deposition of Films," Chem. Mater., Vol. 4, No. 4, pp. 749-752, 1992;
- Hybertson, B.M. et al., "Deposition of Palladium Films by a Novel Supercritical Fluid Transport-Chemical Deposition Process," Mat. Res. Bull., Vol. 26, pp. 1127-1133, 1991; and
- Ziger, D.H. et al., "Compressed Fluid Technology: Application to RIE-Developed Resists," AIChE Jour., Vol. 33, No. 10, pp. 1585-1591, October 1987.

This Information Disclosure Statement under 37 C.F.R. §§ 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that anyone or more of these citations constitutes prior art.

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 11/19/01

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